

PATENT NUMBER and  
ISSUE DATE

U.S. UTILITY Patent Application

APPL NUM	FILING DATE	CLASS	SUBCLASS	GAU	EXAMINER
10020047	12/07/2001	430	5	1756	ROSASCO

\*\*APPLICANTS: Rothschild Mordechai; Liberman Vladimir;

\*\*CONTINUING DATA VERIFIED:  
THIS APPLN CLAIMS BENEFIT OF 60/317,694 09/06/2001

\*\* FOREIGN APPLICATIONS VERIFIED:

PG-PUB DO NOT PUBLISH ☐

RESCIND ☐

Foreign priority claimed ☐ yes ☒ no  
35 USC 119 conditions met ☐ yes ☒ no

ATTORNEY DOCKET NO

Verified and Acknowledged Examiners's initials

M0635/7073

TITLE : Attenuating phase shift mask for photolithography

U.S. DEPT. OF COMM./PAT. & TM.-PTO-436L (Rev. 12-94)

NOTICE OF ALLOWANCE MAILED

Assistant Examiner

CLAIMS ALLOWED

Total Claims Printed Claim for O.G.

ISSUE FEE

Amount Due Date Paid

DRAWING

Sheet Draw. Figs. Draw. Print Fig.

Primary Examiner

PREPARED FOR ISSUE

Application Examiner

☐ TERMINAL  
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